EUVL Regional Review - Europe.

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Damage of multilayer optics with varying capping layers induced by focused extreme ultraviolet beam

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Stability of EUV multilayer coatings to low energy alpha particles bombardment

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Dublin: UCD & DCU

UCD

- Colliding plasma work for 13.5 nm
- Time-resolved spectra at 6.x nm
- Dilute medium & high-Z targets for 6.x nm
- DPP studies at 6.x nm



- Spectroscopy & source development for "Water Window"
- New grant proposals in preparation......

DCU

- Colliding Plasma
- Pulsed Laser Deposition Studies



Zurich

- <u>ETHZ</u> Laboratory for Energy Conversion (LEC)
- Research on droplet-based laser-produced plasma sources.
 Adlyte (spin-off company) commercializes technology.
- Prototype EUV sources for actinic metrology have been designed, developed and tested over the last years.
- Source brightness of 350 W/mm2sr and a EUV pulse-to-pulse stability of 3% (σ).
- New IF module installed and cleanliness studied after IF.
- Recent focus on extension of operating time, source cleanliness and new fuels.

ASML

- Advanced Research Centre for Nano-Lithography
- ARCNL Established with FOM, NOW, UvA & VU
- Director Prof. dr. Joost Frenken
- Jan 2014 start















Prague

- Multiple Centres of Activity
- > 50 active researchers + ~20 students
- Optics, sources, applications
- Plasma diagnostics
- Universities, Institutes + RIT Europe









High average power, pulsed LASErs

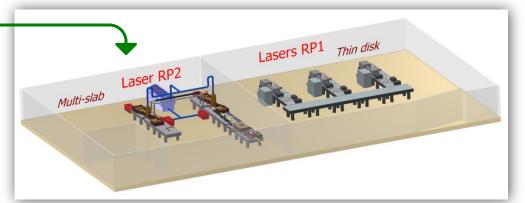


- Project led by the Institute of Physics ASCR
- Financed by the Research and Development for Innovation Operational Program (ERDF)
- Research center of international importance
- Applications of DPSSL in high-tech industry
- Lasers with breakthrough parameters
- Synergy with ELI Beamlines









Laser technologies

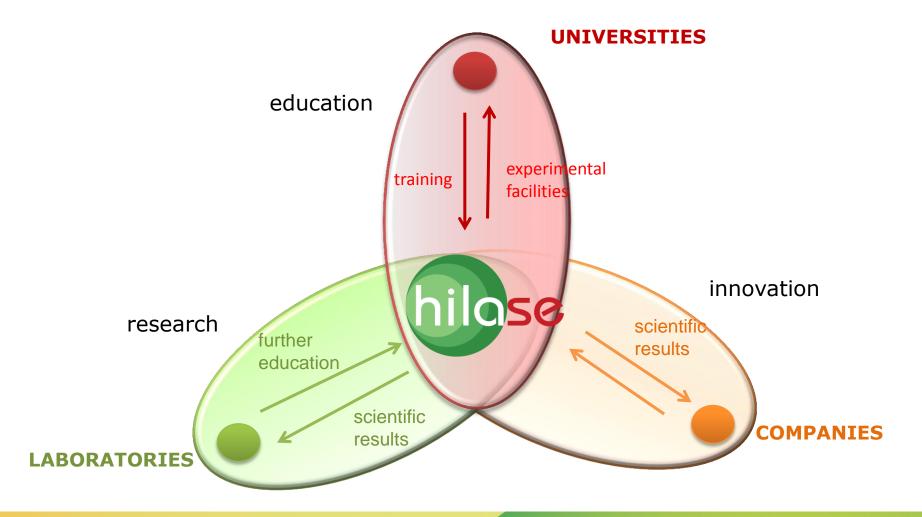






Mission











In-house R&D: 12/2013











June 2014











Thin-disk laser lab clean & ready









